New PCT National Phase Application
Docket No. 12480-000102/US
10/526470
IN THE CLAIMS PT01 Rec'd PCT/PTC 0 3 MAR 2005

This is a complete and current listing of the claims, marked with status identifiers in parentheses. The following listing of claims will replace all prior versions and listings of claims in the application.

- 1. (Previously Presented) A field-effect transistor, comprising:
- a ferromagnetic layer, having a film thickness of 50 nm or less, which is made of a Ba-Mn oxide showing ferromagnetism at 0°C or higher;
- a dielectric layer made of a dielectric material or a ferroelectric material, said ferromagnetic layer and said dielectric layer being bonded to each other, wherein

the field-effect transistor has a bottom-gate structure.

- 2. (Original) The field-effect transistor as set forth in claim 1, wherein the ferromagnetic layer is made of a Ba-Mn oxide whose composition is represented by  $(La_{1-x}Ba_x)$  MnO<sub>3</sub> where x satisfies 0.05<x<0.3.
- 3. (Original) The field-effect transistor as set forth in claim 1, wherein the ferromagnetic layer is made of a Ba-Mn oxide whose composition is represented by ( $La_{1-x}Ba_x$ ) MnO<sub>3</sub> where x satisfies 0.10<x<0.3.

- 4. (Currently Amended) The field-effect transistor as set forth in claim 1, 2, or 3, wherein the dielectric material or the ferroelectric material is BaTiO<sub>3</sub>, SrTiO<sub>3</sub>, (Ba<sub>1-y</sub>Sr<sub>y</sub>) TiO<sub>3</sub>, PbTiO<sub>3</sub>, Pb (Zr1-zTiz) TiO<sub>3</sub>, or Al<sub>2</sub>O<sub>3</sub>, where y satisfies 0<y<1 and z satisfies 0<z<1.
- 5. (Currently Amended) The field-effect transistor as set forth in claim 1, 2, or 3, wherein the dielectric material or the ferroelectric material is BaTiO<sub>3</sub>, SrTiO<sub>3</sub>, (Ba<sub>1-y</sub>Sr<sub>y</sub>) TiO<sub>3</sub>, PbTiO<sub>3</sub>, or Al<sub>2</sub>O<sub>3</sub>, where y satisfies 0 < y < 1.

## 6. (Cancelled)

- 7. (New) The field-effect transistor as set forth in claim 2, wherein the dielectric material or the ferroelectric material is BaTiO<sub>3</sub>, SrTiO<sub>3</sub>, (Ba<sub>1-y</sub>Sr<sub>y</sub>) TiO<sub>3</sub>, PbTiO<sub>3</sub>, Pb (Zr1-zTiz) TiO<sub>3</sub>, or Al<sub>2</sub>O<sub>3</sub>, where y satisfies 0 < y < 1 and z satisfies 0 < z < 1.
- 8. (New) The field-effect transistor as set forth in claim 2, wherein the dielectric material or the ferroelectric material is  $BaTiO_3$ ,  $SrTiO_3$ ,  $(Ba_{1-y}Sr_y)$   $TiO_3$ ,  $PbTiO_3$ , or  $Al_2O_3$ , where y satisfies 0 < y < 1.
- 9. (New) The field-effect transistor as set forth in claim 3, wherein the dielectric material or the ferroelectric material is

BaTiO<sub>3</sub>, SrTiO<sub>3</sub>, (Ba $_{\frac{1}{3}}$ -ySry) TiO<sub>3</sub>, PbTiO<sub>3</sub>, Pb (Zr1-zTiz) TiO<sub>3</sub>, or Al $_2$ O<sub>3</sub>, where y satisfies 0<y<1 and z satisfies 0<z<1.

10. (New) The field-effect transistor as set forth in claim 3, wherein the dielectric material or the ferroelectric material is  $BaTiO_3$ ,  $SrTiO_3$ ,  $(Ba_{1-y}Sr_y)$   $TiO_3$ ,  $PbTiO_3$ , or  $Al_2O_3$ , where y satisfies 0 < y < 1.